

REMARKS

By this Amendment, claim 15 has been amended. Applicant does not, by this amendment, intend to abandon subject matter of the claims as originally filed or later presented. No new matter has been added. Claims 1-23 are pending in this patent application. Reconsideration of the rejections in view of the remarks below is requested.

The Office Action rejected claim 15 under 35 U.S.C. §102(b) as being anticipated by U.S. Patent No. 6,482,558 to Singh et al. ("Singh et al."). Applicant respectfully traverses the rejection, without prejudice.

Applicant respectfully submits that the cited portions of Singh et al. fail to disclose, teach or suggest a method of fabricating a device using a lithographic process, comprising, *inter alia*, exposing a part of the resist to ultraviolet radiation while applying an electric field across the resist as recited in independent claim 15.

Singh et al. merely disclose an electron beam recorder for making a photomask. See, e.g., Singh et al., col. 1, lines 50-56 and col. 3, lines 23-35. Singh et al. however fail to disclose exposing a part of the resist to ultraviolet radiation while applying an electric field across the resist as recited in claim 15 since Singh et al. merely disclose exposing resist with an electron beam. Thus, the cited portions of Singh et al. fail to disclose, teach or suggest claim 15 and is allowable for similar reasons as, for example, allowed claim 1.

Therefore, for at least the above reasons, the cited portions of Singh et al. fail to disclose, teach or suggest all the features recited by independent claim 15. Claims 20-21 depend from independent claim 15 and are, therefore, patentable for at least the same reasons provided above related to claim 15, and for the additional features recited therein. As a result, Applicant respectfully submits that the rejection under 35 U.S.C. §102(b) of claim 15 in view of Singh et al. should be withdrawn and the claims allowed.

Applicant appreciates the allowance of claims 1-14, 16-19 and 23. In reply to the Examiner's statement of reasons for the allowed subject matter, Applicant respectfully submits that the subject matter of the allowed claims are patentable for their respective recitations of claimed combinations as a whole, without any particular criticality or distinguishing feature being attributable to any one or more of such features, and without any narrowing interpretation being imposed on any of such features. As such, Applicant respectfully submits that no one element or limitation in particular should be deemed to impart to or be required for patentability of the claims. Furthermore, Applicant respectfully

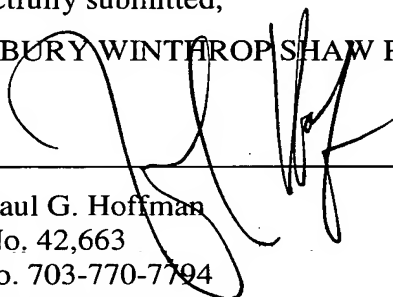
submits that the independent claims are all separately patentable from each other and are patentable for the subject matter specifically recited as a whole in each of those claims. Applicant also submits that the dependent claims are allowable for their dependence on the allowed independent claims and further for the additional subject matter recited in each of those dependent claims.

All objections and rejections having been addressed, it is respectfully submitted that the present application is in condition for allowance. If questions relating to patentability remain, the Examiner is invited to contact the undersigned to discuss them.

Should any fees be due, please charge them to our deposit account no. 03-3975, under our order no. 081468/0309171. The Commissioner for Patents is also authorized to credit any over payments to the above-referenced deposit account.

Respectfully submitted,

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